

AGENDA



SUSS TECHNOLOGY FORUM 2019

ADVANCED PHOTOMASK SOLUTIONS TOWARD 14/10 NM

You are cordially invited to the SUSS Photomask Workshop taking place at the Jumeirah Himalayas Hotel at 8:30 -12:30 on Wednesday, March 20, 2019, during the first day of SEMICON China.

World renowned experts from the mask industry including DNP, FujiFilm, Mitsui Chemical, NuFlare, Photronics, Zeiss and SUSS MicroTec will give their perspectives on challenges and solutions beyond 14 nm and 10 nm mask fabrication and maintenance inside wafer fabs. The SUSS Photomask Workshop will also provide opportunities to network with peers within the photo-lithography and -mask community.

Date: Wednesday, March 20th, 2019, 8:30am – 12:30pm

Location: Jumeirah Himalayas Hotel (next to Semicon China)

Meeting room: Ru Function Room, level 2

1108 Meihua Rd | Shi Ji Gong Yuan

Pudong Xinqu | Shanghai Shi, China



Mitsui Chemicals



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Attendance is free of charge.

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Moderator: Yuan Zhang, Director Photomask Equipment, SUSS MicroTec Inc.

- 08:30am** **Opening Remark**
Dr. Franz Richter, CEO, SUSS MicroTec
- 08:35am** **Multi-Beam Mask Writer for Advanced Patterning**
Naoya Hayashi, Research Fellow, DNP
- 09:00am** **Enabling Wafer Solutions through Mask Collaboration**
Angus Chin, Associate VP, Photonics

SESSION 1: ADVANCED MASK MANUFACTURING

- 09:25am** **NuFlare VSB Mask Writers for 14 nm and 10 nm Technology Node**
Hideki Matsui, Group Manager, NuFlare
- 09:45am** **Advanced Acoustic Streaming Technology for Mask Bake and Develop**
Manfred Zimmermann, Product Manager, SUSS MicroTec
- 10:05am** **Current Status and Prospect of EB Resist for 14 nm and 10 nm Mask Application**
Koji Shirakawa, R&D Manager, FujiFilm
- 10:25am** **Advanced Mask Cleaning Reducing Pattern and Surface Damage**
Uwe Dietze, Senior Director, SUSS MicroTec
- 10:45am** **Coffee Break**

SESSION 2: ADVANCED MASK MAINTENANCE

- 11:00am** **Mask Pellicle Development for 14 nm and 10 nm**
Daiki Taneichi, Senior Researcher, Mitsui Chemical
- 11:20am** **Local Pellicle Glue Removal Eliminating Need for Aggressive Final Clean**
Dr. Davide Dattilo, Process Scientist, SUSS MicroTec
- 11:40am** **E-beam and Defects – a Superlative Nano Playground**
Dr. Markus Waiblinger, Senior Product Manager, Carl Zeiss
- 12:00pm** **Mask Pattern Defect Inspection Tool Technology**
Yoshitaka Yasui, Group Manager, NuFlare
- 12:20pm** **Closing Statement**
Yuta Nagai, General Manager, SUSS MicroTec
- 12:30pm** **End of Forum**